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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

INVENTORS: J. Westwood

SERIAL NO.: 09/642,620

GROUP ART UNIT: 1773

FILED: 08/18/00

EXAMINER: K. Bernatz

FOR: High Moment Films With Sub-Monolayer Nanolaminations  
Retaining Magnetic Anisotropy After Hard Axis Annealing

*Handwritten signature/initials*

Commissioner of Patents and Trademarks  
Washington, D.C. 20231

RESPONSE TO OFFICE ACTION

Dear Sir:

In response to the Office Action dated October 23, 2002, please enter the following amendment and remarks in the above identified patent application.

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TECHNOLOGY CENTER 1700

In the claims:

Please amend claim 1 as follows:

*sub B17*

1.(AMENDED) A magnetic film comprising:  
a magnetic alloy T-M-X wherein T is at least 90 atomic percent of one element selected from the group consisting of Fe, Co, and Ni, M is selected from the group consisting of B, Al, Si, P, Ti, V, Cr, Cu, Ga, Ge, Zr, Nb, Mo, Ru, In, Sn, Hf, and Ta, and X is selected from the group consisting of N, O, and C; and  
at least a single nanolamination of a material selected from the group consisting of Al<sub>2</sub>O<sub>3</sub>, SiO<sub>2</sub>, ZrO<sub>2</sub>, yttria-stabilized ZrO<sub>2</sub>, TiO<sub>2</sub>, HfO<sub>2</sub>, Ta<sub>2</sub>O<sub>5</sub>, Si<sub>3</sub>N<sub>4</sub>, AlN, B<sub>4</sub>C, SiC, Si<sub>4</sub>N<sub>4</sub>, Ta, Zr, and Hf.

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